



THE  
HONG KONG  
UNIVERSITY OF  
SCIENCE &  
TECHNOLOGY

香港  
科技  
大學

12/F World Shipping Centre,  
7 Canton Road, Tsimshatsui,  
Kowloon, Hong Kong.  
Facsimile No.

Vice-Chancellor and President  
Professor Chia-Wei Woo, BS, MA, PhD

**Press Release**

**Professor of Chemistry**  
**Appointed for the Hong Kong University of Science and Technology**

The Hong Kong University of Science and Technology today announces the appointment of Prof. Hiroyuki Hiraoka (平岡弘之教授), presently Senior Research Staff Member of the Polymer Science and Technology Department at the IBM Almaden Research Center in San Jose, California, as Professor of Chemistry.

Professor Hiraoka has researched widely in advanced materials. His current research interests include laser photoetching, studies in new resist preparations and new process developments in microlithography, photochemistry and radiation chemistry of polymers, and basic photochemistry of simple molecules. He has published more than 140 papers and book chapters, made numerous presentation, and holds 16 patents. His paper in 1981 initiated the UV-hardening/photostabilization process of resists images, an important process which has become a standard practice in industry. His patent and his publication in macromolecules were the first to report the use of PMGI as a resist material.

Professor Hiraoka earned his BS, MS, and PhD from Kyoto University. He also holds an MBA from Golden Gate University. Professor Hiraoka has received many awards from the IBM Corporation, the latest being the Outstanding Technical Achievement Award on UV-hardening of resists presented to him in 1987. During 1987 and 1988 he was a Visiting Adjunct Professor at Colorado State University. In 1990, on leave of absence from IBM Research, he spent half a year as a Visiting Professor in Universite de Bordeaux I.

Professor Hiraoka is married with two sons.

The Hong Kong University of Science and Technology  
21 June 1990

For inquiry, contact Office of Public Affairs, 3021450.

平岡弘元

**Prof. Hiroyuki Hiraoka, Professor of Chemistry**

Prof. Hiroyuki Hiraoka, presently Senior Research Staff Member of the Polymer Science and Technology Department at the IBM Almaden Research Center in San Jose, California, has been appointed Professor of Chemistry.

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Professor Hiraoka earned his B.S., M.S., and Ph.D. from Kyoto University. He also holds an M.B.A. from Golden Gate University. Professor Hiraoka has received many awards from the IBM Corporation, the latest being the Outstanding Technical Achievement Award on UV-hardening of resists presented to him in 1987. During 1987 and 1988 he was a Visiting Adjunct Professor at Colorado State University. In 1990 he spent half a year as a Visiting Professor in Universite de Bordeaux 1 on leave of absence from IBM Research. 弘元博士 }  
博士 }  
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